

ABSTRACT

TITLE OF INVENTION: REFLECTIVE MASK BLANK AND METHOD FOR MANUFACTURING THE SAME

A reflective mask blank having auxiliary marks formed with a simple structure and little risk of particle generation in a reference mark is provided. The reflective mask blank including at least a substrate, a multilayer reflective film and reflecting exposure light, and an absorber film on the multilayer reflective film, the reflective mask blank further includes a reference mark formed on a surface on a same side as the multilayer reflective film, the reference mark consists of a main mark serving as a reference position for a defect position, and an auxiliary mark group disposed around the main mark, the auxiliary mark group consists of a plurality of auxiliary marks formed at intervals from one another to extend in at least one direction starting from the main mark, and the plurality of auxiliary marks are all formed in a same shape and in a same orientation.

[Fig. 3]